Tracking of structural defects induced by Eu-doping in β -Ag₂MoO₄: their influences on electrical properties

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SUPPORTING INFORMATION



Figure S1 - Rietveld refinement fitting of the XRD for the samples a) Pure, b) 4Eu, c)8Eu, and d) 16Eu.



Figure S2 - Williamson-Hall plots for the samples a) Pure, b) 4Eu, c)8Eu, and d) 16Eu.



Figure S3 - Deconvolution of the A_{1g} Raman mode for the samples a) Pure, b) 4Eu, c)8Eu, and d) 16Eu.



Figure S4 - E_{gap} determination for the samples a) Pure, b) 4Eu, c)8Eu, and d) 16Eu.



Figure S5 - Equivalent circuit model for theoretical adjustments of the data for the Nyquist plot combining ideal resistors, capacitors, and inductors. R_{ef} is the contact effective electrical resistance, C_{ef} is the contact effective electrical capacitance. R_{gb} is the grain boundary electrical resistance, C_{gb} is the is the grain boundary electrical capacitance. CPE $_{ef \text{ contact}}$ is the Constant Phase Element (CPE) for the contact and CPE_t the Constant Phase Element (CPE) for the raps.

Sample	Lattice parameters		Rietveld parameters			
	V (ų)	phase (%)	R _{bragg}	R _{wp}	χ²	
Pure	806.73±10	100.0	3.63	12.14	3.55	
4Eu	807.36±23	100.0	0.89	2.27	1.68	
8Eu	807.54±80	100.0	1.16	0.86	0.77	
16Eu	808.18±21	100.0	0.73	0.72	0.74	

Table S1 - Rietveld refinement fitting and lattice parameters for all samples of the $\beta\text{-}Ag_2MoO_4$ system.

Table S2 - XRD and Raman FWHM for all samples of the β -Ag₂MoO₄ system.

Samples	XRD FWHM	Raman FWHM
Pure	0.14	9.8
4Eu	0.17	9.9
8Eu	0.12	10.8
16Eu	0.12	11.0

Table S3 – Atomic coordinates, occupancy factor and anisotropic thermal factor (B_{eq}).

Pure	Site	Np	х	у	Z	Atom	Occupancy	B _{eq}
	Ag1	16	0.62500	0.62500	0.62500	Ag⁺	0.99	3.91
	Eu1	16	0.62500	0.62500	0.62500	Eu ³⁺	0.01	0.01
	Mo1	8	0.00000	0.00000	0.00000	Mo ⁶⁺	1.00	1.99
	01	32	0.36616	0.30897	0.36616	O ²⁻	1.00	20.0
4Eu	Site	Np	х	У	Z	Atom	Occupancy	Beq
	Ag1	16	0.62500	0.62500	0.62500	Ag⁺	0.99	2.75
	Eu1	16	0.62500	0.62500	0.62500	Eu ³⁺	0.01	0.03
	Mo1	8	0.00000	0.00000	0.00000	Mo ⁶⁺	1.00	1.13
	01	32	0.32423	0.38366	0.32423	O ²⁻	1.00	19.9
8Eu	Site	Np	х	у	Z	Atom	Occupancy	Beq
	Ag1	16	0.62500	0.62500	0.62500	Ag⁺	0.99	3.37
	Eu1	16	0.62500	0.62500	0.62500	Eu ³⁺	0.01	0.01
	Mo1	8	0.00000	0.00000	0.00000	Mo ⁶⁺	1.00	1.59
	01	32	0.32436	0.38437	0.32436	O ²⁻	1.00	19.9
16Eu	Site	Np	х	у	Z	Atom	Occupancy	Beq
	Ag1	16	0.62500	0.62500	0.62500	Ag⁺	0.99	3.39
	Eu1	16	0.62500	0.62500	0.62500	Eu ³⁺	0.01	0.12
	Mo1	8	0.00000	0.00000	0.00000	Mo ⁶⁺	1.00	1.72
	01	32	0.32309	0.38490	0.32309	O ²⁻	1.00	19.9

Table S4 – CIE coordinates and CCT of the samples

Samples	х	У	ССТ (К)	Color purity (%)
Pure	0.3832	0.3197	4800	-
4Eu	0.5042	0.3330	3964	30.73
8Eu	0.5213	0.3222	4886	36.46
16Eu	0.5501	0.3200	6130	43.98